

U.S.S.N. 10,810,912

Specification Amendments

Please replace the paragraph 0043 with the following re-written paragraph:

0043        During the CVD deposition process of step 5, the seasoning film 30 repels the formation of amorphous silicon and other material residues on the interior surfaces of the chamber 10. Therefore, after completion of the CVD deposition process, these residues are readily evacuated from the chamber 10 with the remaining process gases using the vacuum pump 20.